Supplementary Information

Crystalline boron monosulfide nanosheets with tunable bandgaps

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Figure S11. Raman mapping of BS nanosheets on Si surface.

Crystal data									
Crystal system, space group	Trigonal, R ⁻ 3m								
Temperature (K)	300								
a, c (Å)	3.05070, 20.3846 (1)								
V (Å ³)	164.30 (1)								
Z	3								
Radiation type	Synchrotron, $\lambda = 1.07900$ Å								
Selected bond lengths (Å) B—B	1.6756 (1)								
Fractional atomic									
coordinates (x, y, z (Å)) and isotropic or equivalent isotropic displacement parameters (U_{iso} (Å ²))		Х	у	Z	U _{iso}				
	S	0.00000	0.00000	0.54110(8)	0.0055(5)				
	В	0.00000	0.00000	0.24969(3)	0.0055(5)				

Table S1. Crystal data for rhombohedral boron monosulfide (r-BS) derived by Rietveld analysis.



Figure S1. B 1s and S 2p binding energies for several compounds reported in the literature.



Figure S2 Calculated electron localization functions (EFLs) of r-BS, boron nitride (BN), and molybdenum disulfide (MoS₂). **a** Cross-sectional ELF images along the (110) plane for r-BS, h-BN, and MoS₂. **b** ELF profiles along the chemical bonds in r-BS, h-BN, and MoS₂. Both r-BS and h-BN show ELF maxima at midpoints between the respective atoms indicative of the formation of covalent bonds, while maximum intensity is observed near the sulfur in MoS₂, consistent with ionic bonding. **c** Three-dimensional ELF surfaces (at isosurfaces values of 0.85) for r-BS, h-BN, and MoS₂. The slightly larger surface contributions of the top and bottom regions of each BS layer are due to the accumulation of charge in the p_z orbitals of sulfur, which explains the slightly negatively charged sulfur suggested by S $2p_{3/2}$ peak position (Fig. 1b).



Figure S3. Scanning electron microscopy (SEM) image of r-BS particles on a Si surface. Incident energy of electron beam: 10 kV. Stacked layers can be seen in the image, as indicated by yellow arrows.



Figure S4. SEM and energy dispersive X-ray spectroscopy (EDX) data for r-BS on a Si surface. **a** SEM image of r-BS on Si surface. **b** EDX of r-BS on Si surface. **c** Elemental maps of r-BS (here, the B: $K_{\alpha 1}$, 2, S: $K_{\alpha 1}$, and Si: $K_{\alpha 1}$ intensities are shown in green, yellow, and white, respectively).



Figure S5. X-ray diffraction (XRD) patterns of r-BS powder before (as prepared) and heating at 725 K in a flow of Ar for 30 min.

Table S2. Calculated effective mass of r-BS and monolayer BS using DFT-LDA. The eigenvalues of the effective mass tensor (m_1 , m_2 , and m_3), as well as the harmonic averaged mass m^* , are shown in units of electron mass (m_e) or hole mass (m_h).

		m_1	m_2	<i>m</i> 3	<i>m</i> *
Bulk r-BS	elec.	2.20	0.56	0.20	0.41
	hole	2.04	2.04	0.23	0.57
Monolayer BS	elec.	2.27	0.16	_	0.29
	hole	15.60	4.47	_	6.95



Figure S6. Ultraviolet-Visible (UV-Vis) absorption spectra for r-BS bulk powder and r-BS nanosheets. a. UV-Vis absorption spectrum of r-BS bulk powder recorded by the diffuse reflectance method using an integration sphere unit. b. UV-Vis absorption spectrum of the BS nanosheets dispersed in acetonitrile measured under transmittance mode using a quartz cell.



Figure S7. Environmental stability of BS nanosheets. **a.** Image of the BS nanosheets prepared using the Scotch-tape method on graphite tape. **b.** XPS profiles of BS nanosheets after exposure to air (the sample is the same as the one shown in panel a). Similar to Fig. 1b, the XPS profile does not show any additional oxide peak, indicating that the BS nanosheets are stable in air. **c** Image of the distilled water droplet on BS nanosheets prepared using the Scotch-tape method on graphite tape. **d** XPS profiles of BS nanosheets after drying the water droplet by evacuating in vacuum for 10 h (the sample is the same as the sample shown in panel c). Similar to Fig. 1b, the XPS profile does not show any additional oxide peak, indicating that the BS nanosheets are stable against water.



Figure S8. Atomic force microscopy (AFM) images of r-BS and 2D BS nanosheets. **a** AFM image of r-BS (before separation). **b** Profile along the line between points A and A' in panel a. **c** AFM image of 2D BS nanosheets (after separation). **d** Profile along the line between B and B' in panel c. **e** AFM image of 2D BS nanosheets (after separation). **f** Profile along the line between C and C' in panel e.



Figure S9. B 1s and S 2p X-ray photoelectron spectra of 2D BS nanosheets on an Au surface (after separation; i.e., removal of the solvent from acetonitrile supernatant by drying on the Au surface).



Figure S10. Raman mapping of as-synthesized r-BS powder on an Si surface. The intensity in each pixel was normalized against the maximum intensity in the range $670-700 \text{ cm}^{-1}$. **a.** Raman mapping at 682.55 cm⁻¹, where the intensity at 682.55 cm⁻¹ was plotted as an image. **b.** Raman mapping at 687.25 cm⁻¹, where the intensity at 682.55 cm⁻¹ was plotted as an image. **c.** Raman spectrum averaged at the indicated area in a (red curve) and b (blue curve), which shows a distinct difference between the peak position. According to the DFT calculation, the Raman peak position of the corresponding mode, E(4), is 709.29 cm⁻¹ for one layer BS, 708.22 cm⁻¹ for two-layer BS, 707.67 cm⁻¹ for three-layer BS, and 705.29 cm⁻¹ for bulk r-BS. Thus, there are 4 different wavenumbers between single layer BS and bulk r-BS, and the peak position depends on the thickness, as in the case of the bandgap. The experimental peak position difference indicates the presence of BS sheets with different thicknesses.



Figure S11. Raman mapping of the BS nanosheets on an Si surface. **a.** Raman intensity mapping, where the integral intensity from $670.48-701.95 \text{ cm}^{-1}$ was plotted as an image. **b.** Raman peak mapping, where the intensity peak frequency in the range of $684-690 \text{ cm}^{-1}$ was plotted as an image (after selecting the peak intensity above 3000 arb. units). Red color positions indicate thin nanosheets, while green color positions indicate thick nanosheets or bulk r-BS (see Figure S10).

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